

AMENDMENTS TO THE ABSTRACT:

Please amend the abstract as follows:

--ABSTRACT

THIN LAYER OF HAFNIUM OXIDE AND DEPOSIT PROCESS

--A thin layer of hafnium oxide or stacking of thin layers comprising hafnium oxide layers for producing surface treatments of optical components, or optical components, ~~characterised in that~~ in which at least one layer of hafnium oxide is in amorphous form with and has a density less than 8 gm/cm^3 . ~~The invention also relates to a process for producing a layer of amorphous hafnium oxide on a substrate, characterised in that the deposit is carried out~~
The layer is formed by depositing on a substrate without energy input to the substrate.

[Figure 1]

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